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TITLE: ELECTRO-CHEMICAL DEPOSITION CELL FOR FACE-UP
PROCESSING OF SINGLE SEMICONDUCTOR SUBSTRATES
INVENTOR: DORDI, ET AL.
EYDDESS MAIL NO.: EV/35103126511S PAGE 10E 15

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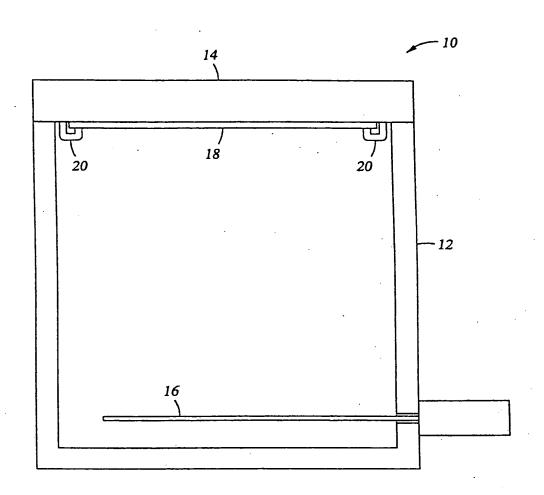
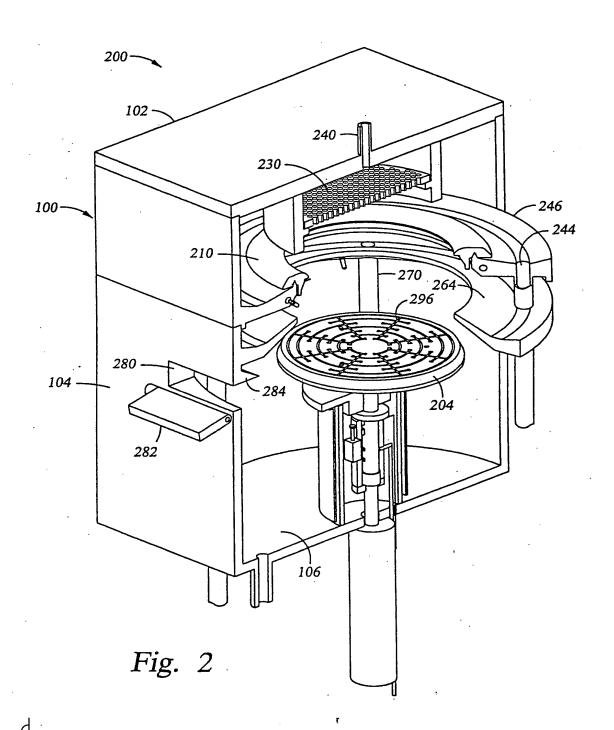


Fig. 1 (PRIOR ART)

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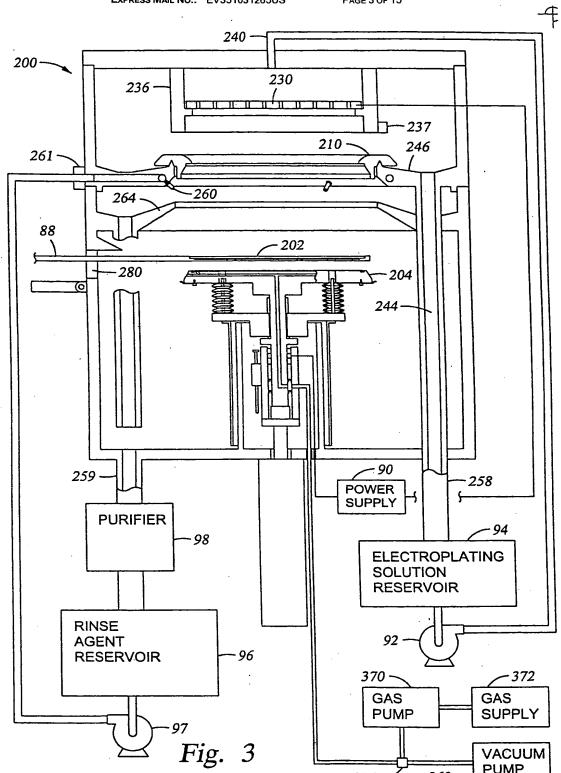


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DORDI, ET AL.

EXPRESS MAIL No.: EV351031265US PAGE 3 OF 15



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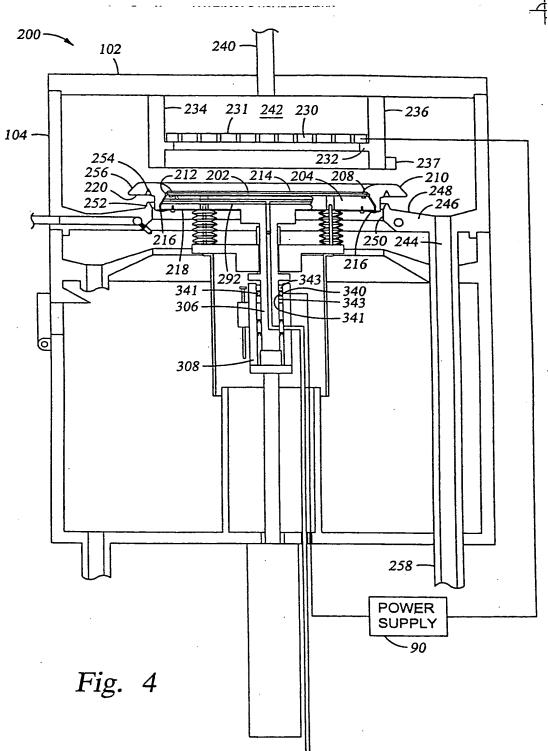
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EXPRESS MAIL No.: EV351031265US PAGE 4 OF 15

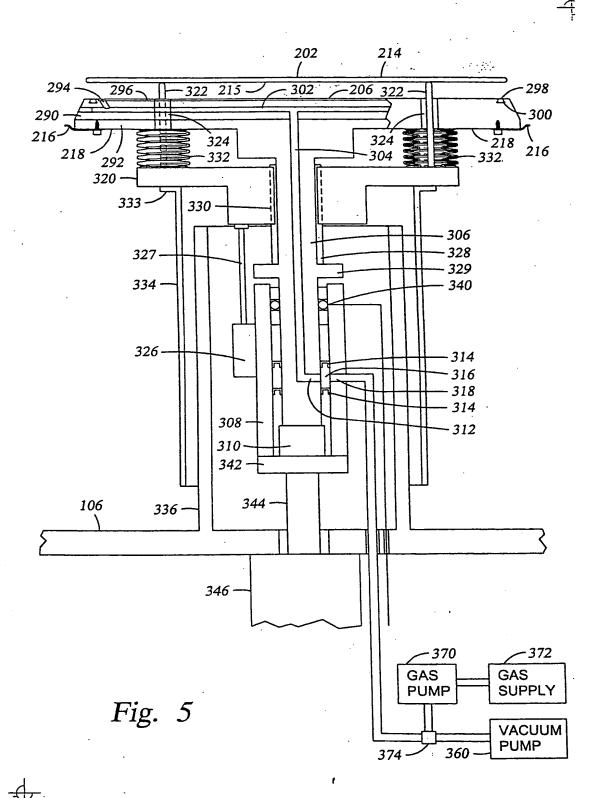


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INVENTOR: DORDI, ET AL. EXPRESS MAIL NO.: EV351031265US

Page 5 of 15



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DORDI, ET AL. INVENTOR:

EXPRESS MAIL No.: EV351031265US

PAGE 6 OF 15

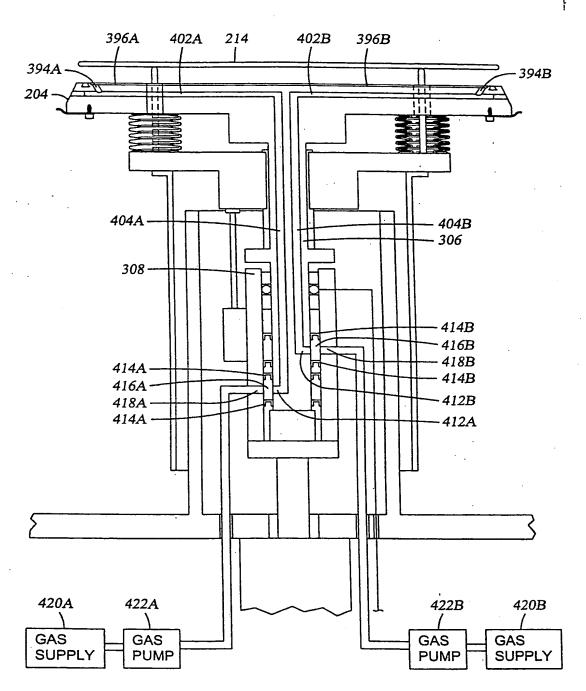
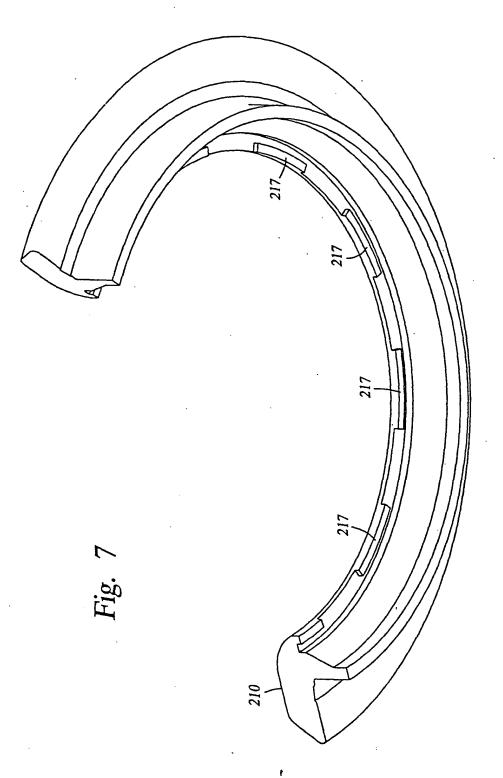
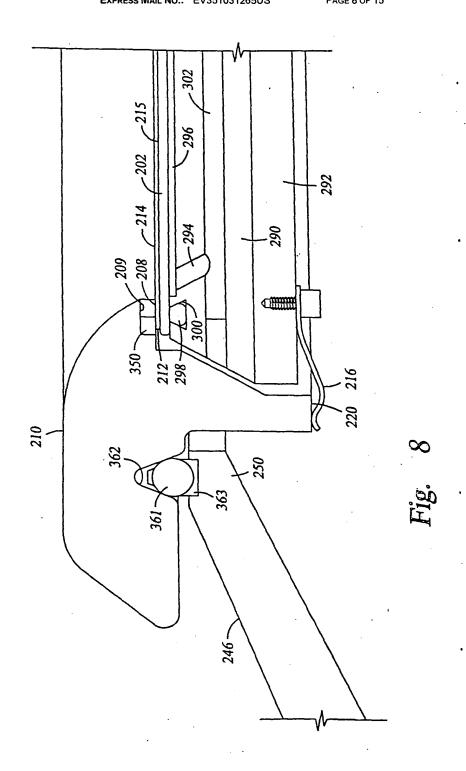


Fig. 6

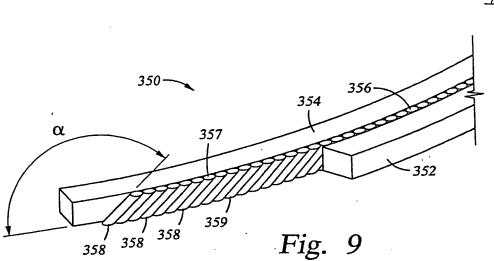
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EXPRESS MAIL NO.: EV351031265US PAGE 7 OF 15

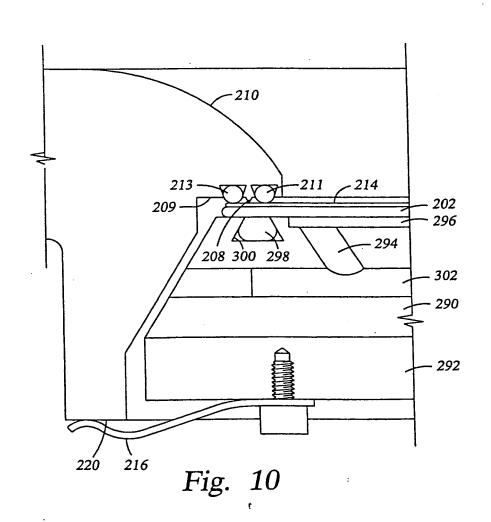


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EXPRESS MAIL NO.: EV351031265US
PAGE 8 OF 15



APPLICANT: APPLIED MATERIALS
TITLE: ELECTRO-CHEMICAL DEPOSITION CELL FOR FACE-UP
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INVENTOR: DORDI, ET AL.
EXPRESS MAIL NO.: EV351031265US PAGE 9 OF 15





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EXPRESS MAIL NO.: EV351031265US PAGE 10 OF 15

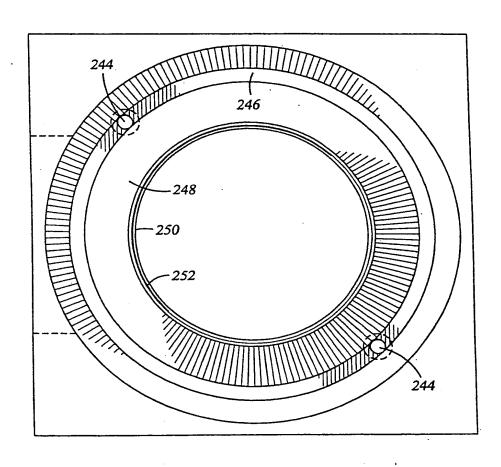
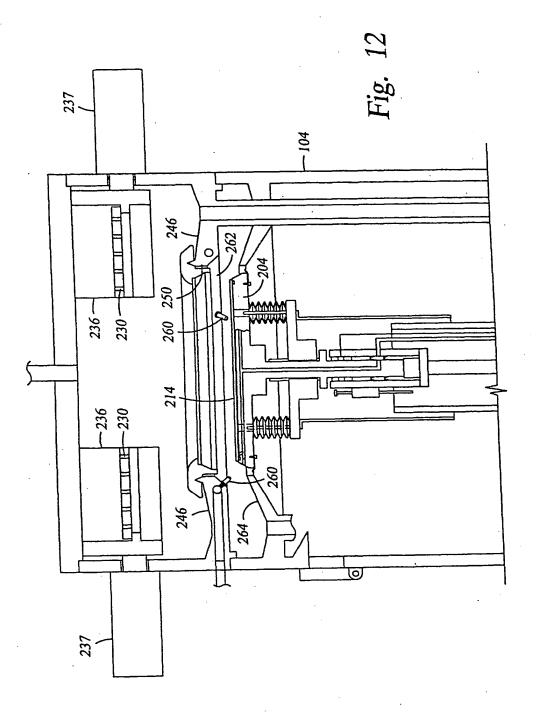
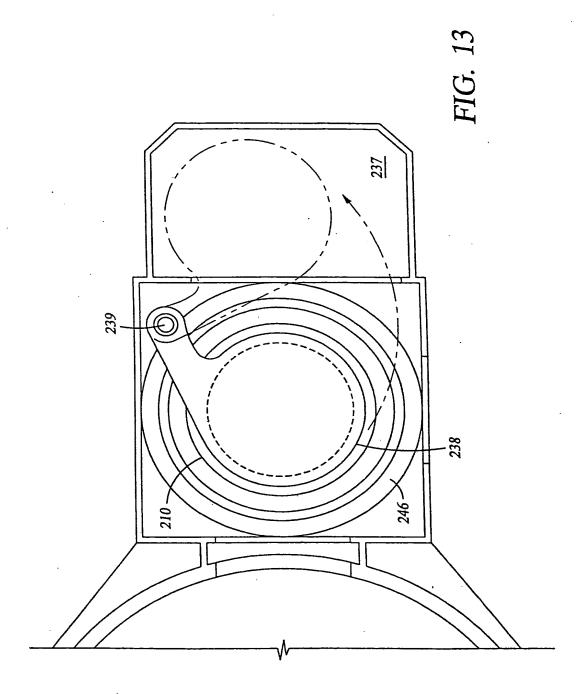


Fig. 11

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INVENTOR: DORDI, ET AL.
EXPRESS MAIL NO.: EV351031265US
PAGE 11 OF 15

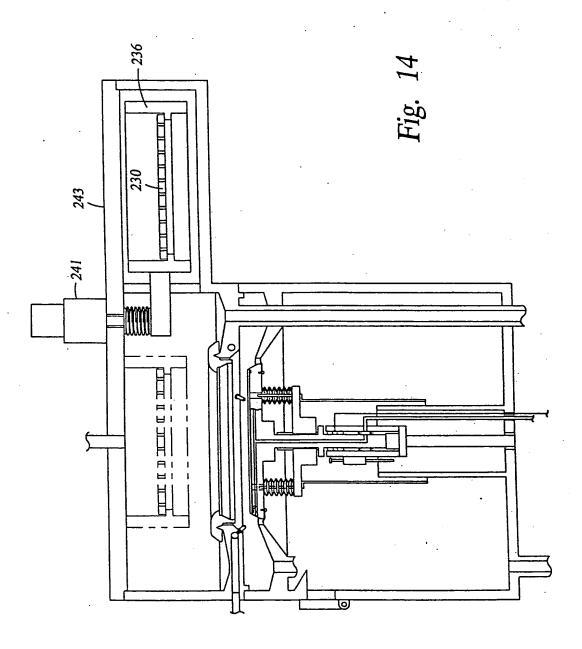


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EXPRESS MAIL NO.: EV351031265US PAGE 12 OF 15



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EXPRESS MAIL NO.: EV351031265US PAGE 13 OF 15



APPLICANT: APPLIED MATERIALS
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EXPRESS MAIL NO.: EV351031265US PAGE 14 OF 15

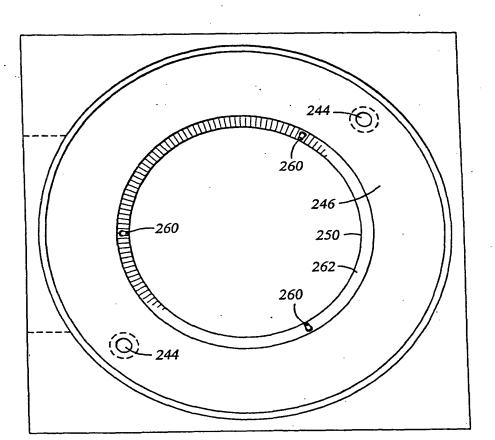


Fig. 15

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EXPRESS MAIL NO.: EV351031265US PAGE 15 OF 15

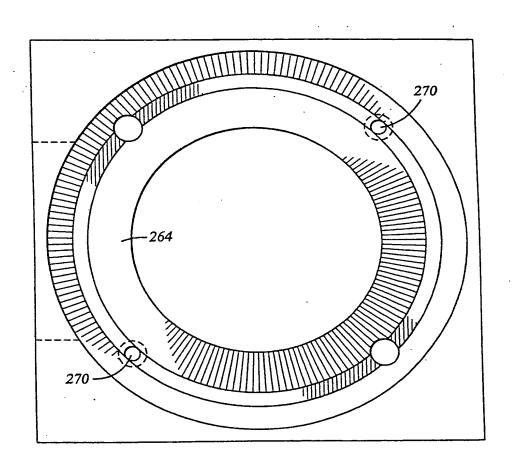


Fig. 16